

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	Markus Schumacher
Serial No. 10/	Filing Date: April 7, 2003
Title of Application:	Method And Device For Depositing A Plurality Of Layers On A Substrate

Mail Stop Non-Fee Amendment  
Commissioner for Patents  
Post Office Box 1450  
Alexandria, VA 22313-1450

**Preliminary Amendment**

Applicant herewith presents its amendment and remarks. Please amend the claims as detailed below.

**In the Claims**

1. (Currently Amended) Process for depositing a multiplicity of layers on a substrate by means of gaseous starting materials, the layer sequence comprising at least one oxide layer and a metal layer deposited thereon, and the layers being deposited in a single process chamber in successive process steps by simply altering the gas phase composition in the process chamber and/or the substrate temperature, characterized in that between the individual process steps the process chamber is pumped out and purged with inert gas, the exhaust-gas which is pumped out of the process chamber (6) being analyzed for residual constituents of the starting material and/or for solvent, and the purging operation being terminated only when this residual gas concentration and/or the solvent concentration drops below a minimum value.

2. (Currently Amended) Apparatus for depositing a multiplicity of layers on a substrate by means of gaseous starting materials, the layer sequence comprising at least one oxide layer and a metal layer deposited thereon, having a process chamber for depositing the layers in successive process steps, it being possible, between the process steps for layer deposition, to alter the gas phase composition in